

<b>INFORMATION DISCLOSURE CITATION</b>		<b>Attorney Docket No.:</b> 46884-5429		<b>Serial No.:</b> 10/551,195			
(Use several sheets if necessary)		<b>Applicants:</b> Seiichi NAGATA		Page 1 of 1			
<b>PTO Form 1449</b>		<b>Filing Date:</b> September 29, 2005		<b>Group Art Unit:</b> Unassigned			
<b>U.S. PATENT DOCUMENTS</b>							
<b>*Examiner Initial</b>		<b>Document Number</b>	<b>Date</b>	<b>Name</b>	<b>Class</b>	<b>Sub Class</b>	<b>Filing Date</b>
<b>FOREIGN PATENT DOCUMENTS</b>							
		<b>Document Number</b>	<b>Date</b>	<b>Country</b>	<b>Class</b>	<b>Sub Class</b>	<b>Translation</b> <b>YES NO</b>
/JL/		10-133047	May 22, 1998	JP			Abstract
/JL/		11-242125	Sept. 7, 1999	JP			Abstract
/JL/		2000-047045	Feb. 18, 2000	JP			Abstract
/JL/		11-014848	Jan. 22, 1999	JP			Abstract
/JL/		10-160950	Jun. 19, 1998	JP			Abstract
/JL/		10-133048	May 22, 1998	JP			Abstract
/JL/		10-300963	Nov. 13, 1998	JP			Abstract
/JL/		61-180449	Aug. 13, 1986	JP			Abstract
/JL/		52-063685	May 26, 1977	JP			Abstract
/JL/		09-292540	Nov. 11, 1997	JP			Abstract
<b>OTHER DOCUMENTS</b>							
(Include name of the author (in CAPITAL LETTERS), title of the article (when appropriate), title of the item (book, magazine, journal, serial, symposium, catalog, etc.) date, page(s), volume-issue number(s), publisher, city and/or country where published.)							
/JL/		M.E. Lines, "Can The Minimum Attenuation of Fused Silica Be Significantly Reduced By Small Compositional Variations? I. Alkali Metal Dopants"; Journal of Non-Crystalline Solids 171, 1994, pp. 209-218					
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<b>Examiner</b>	/Jonathan Langman/				<b>Date Considered</b> 12/30/2008		
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